10/099,981 CA Reg. File
9-8-05 Struc. search

Form (I) and Maleic anhydride or Maleimide derivative

2003:20985 CAPLUS
DN 138:98193
TI Positive resist composition
IN Mizutani, Kazuyoshi; Kanna, Shinichi
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 93 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1273969	A2	20030108	EP 2002-14079	20020701
	EP 1273969	A3	20031022		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
	JP 2003015297	A2	20030115	JP 2001-202240	20010703
	JP 2003015299	A2	20030115	JP 2001-202242	20010703
	JP 2003015300	A2	20030115	JP 2001-202243	20010703
	US 2003134224	A1	20030717	US 2002-187291	20020702
	US 6878502	B2	20050412		
PRAI	JP 2001-202240	A	20010703		
	JP 2001-202242	A	20010703		
	JP 2001-202243	A	20010703		

8/19/02

AB A pos. resist composition comprises (A) a resin which comprises a specified repeating units and (B) a compound capable of generating an acid upon irradiation with one of an actinic ray and a radiation. The present invention relates to a pos. resist composition capable of forming fine patterns with use of a vacuum UV ray having a wavelength ≤ 160 nm.

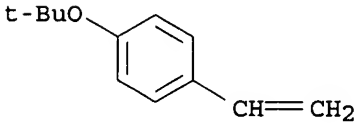
IT **483349-12-8P 483349-13-9P 483349-15-1P 483349-16-2P**
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos. resist composition for vacuum UV photolithog. containing)

RN 483349-12-8 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene, 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol and 2,5-furandione (9CI) (CA INDEX NAME)

FD 7/2/02

CM 1

CRN 95418-58-9
CMF C12 H16 O



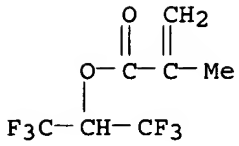
(I) & (VII) & ⇒CO2

✓ ✓ I + II + (VII) +

MAL. ANHY

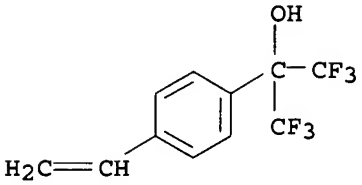
CM 2

CRN 3063-94-3
CMF C7 H6 F6 O2



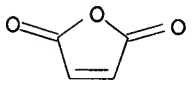
CM 3

CRN 2386-82-5
CMF C11 H8 F6 O



CM 4

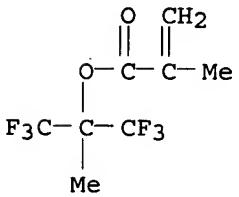
CRN 108-31-6
CMF C4 H2 O3



RN 483349-13-9 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 2,2,2-trifluoro-1-methyl-1-(trifluoromethyl)ethyl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene, 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol, ethyl 2-propenoate and 2,5-furandione (9CI) (CA INDEX NAME)

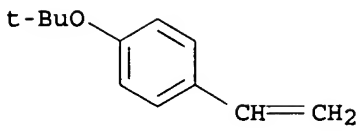
CM 1

CRN 354818-13-6
CMF C8 H8 F6 O2



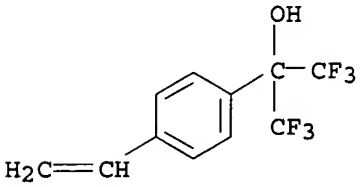
CM 2

CRN 95418-58-9
CMF C12 H16 O



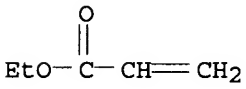
CM 3

CRN 2386-82-5
CMF C11 H8 F6 O



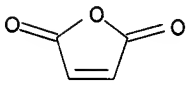
CM 4

CRN 140-88-5
CMF C5 H8 O2



CM 5

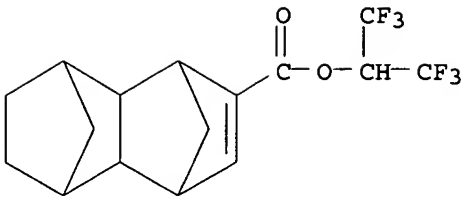
CRN 108-31-6
CMF C4 H2 O3



RN 483349-15-1 CAPLUS
CN 1,4:5,8-Dimethanonaphthalene-2-carboxylic acid, 1,4,4a,5,6,7,8,8a-octahydro-, 2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene, 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol, 2,5-furandione and 2,2,2-trifluoro-1-methyl-1-(trifluoromethyl)ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

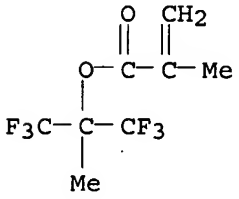
CM 1

CRN 483349-14-0
CMF C16 H16 F6 O2



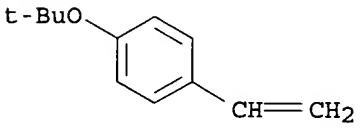
CM 2

CRN 354818-13-6
CMF C8 H8 F6 O2



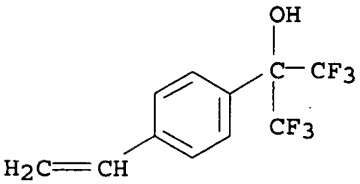
CM 3

CRN 95418-58-9
CMF C12 H16 O



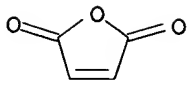
CM 4

CRN 2386-82-5
CMF C11 H8 F6 O



CM 5

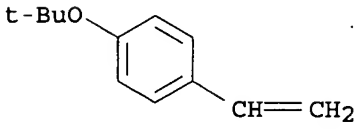
CRN 108-31-6
CMF C4 H2 O3



RN 483349-16-2 CAPLUS
CN 2-Propenoic acid, 2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene, 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol, 2,5-furandione and 1,1,1-trifluoro-2-(trifluoromethyl)-4-penten-2-ol (9CI) (CA INDEX NAME)

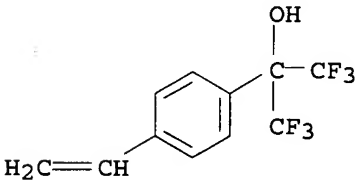
CM 1

CRN 95418-58-9
CMF C12 H16 O



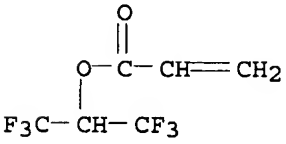
CM 2

CRN 2386-82-5
CMF C11 H8 F6 O



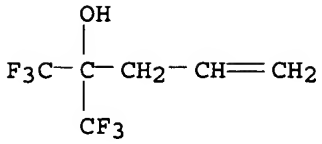
CM 3

CRN 2160-89-6
CMF C6 H4 F6 O2



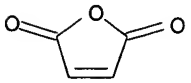
CM 4

CRN 646-97-9
CMF C6 H6 F6 O



CM 5

CRN 108-31-6
CMF C4 H2 O3



L10 ANSWER 2 OF 4 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1990:554009 CAPLUS
DN 113:154009
TI Aromatic polycarbonate-polystyrene compositions for optical materials
IN Takahashi, Yosuke; Oshima, Kensho; Sekimoto, Kenichi
PA Tosoh Corp., Japan
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02120354	A2	19900508	JP 1988-270938	19881028
PRAI JP 1988-270938		19881028		

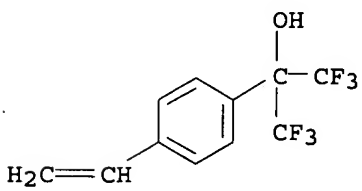
AB The title compns., useful for optical recording materials such as digital audio disks, contain a polycarbonate I (R1, R2 = H, C1-6 alkyl, Ph; A = II, 1,5-decalindiyl, III; m, n = ≥1) and a copolymer of styrene 1-95, maleic anhydride (IV) 1-50, and p-(H2C:CH)C6H4C(CF3)2OH (V) 1-50 mol %. A blend of 60 weight % I (R1, R2 = Me; A = II; m/n = 57/43) (VI) and 40 weight % (mol) 15:75:10 IV-styrene-V copolymer gave injection-molded disks which showed light transmittance (500 nm) 89%, birefringence 3 nm, and heat distortion temperature 143°, vs. 89, 50, and 155, resp., for VI.

IT **129558-09-4**
RL: USES (Uses)
(blends with polycarbonates, transparent, for optical materials)

RN 129558-09-4 CAPLUS
CN 2,5-Furandione, polymer with ethenylbenzene and 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

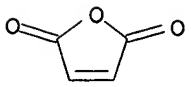
CM 1

CRN 2386-82-5
CMF C11 H8 F6 O



CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 100-42-5
CMF C8 H8

$H_2C{=}CH{-}Ph$

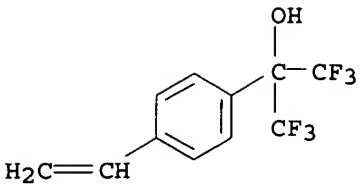
L10 ANSWER 3 OF 4 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1990:533846 CAPLUS
DN 113:133846
TI Aromatic polycarbonate-polystyrene blends for optical materials
IN Takahashi, Yosuke; Oshima, Kensho; Sekimoto, Kenichi
PA Tosoh Corp., Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 02120356	A2	19900508	JP 1988-270940	19881028
PRAI	JP 1988-270940		19881028		

AB The title blends, useful for optical recording materials such as digital recording disks, comprise polycarbonates prepared from phosgene, neopentyl glycol (I), and a bisphenol (HOZ)2CR1R2 (Z = p-C6H4; R1, R2 = H, C1-6 alkyl, Ph) and copolymers of styrene, p-(H2C:CH)C6H4C(CF3)2OH (II), and maleic anhydride (III). A blend of 60% 0.85:0.15:1 (mol) bisphenol A-I-phosgene copolymer (IV)and 40% 0.75:0.1:0.15 (mol) styrene-II-III copolymer gave injection-molded disks (thickness 1.2 mm) having light transmittance (500 nm) 89%, birefringence 2 nm, and heat distortion temperature 120°, vs. 89, 47, and 125, resp., for disks of IV.
IT **129558-09-4**
RL: USES (Uses)
(blends with polycarbonates, transparent, for optical materials)
RN 129558-09-4 CAPLUS
CN 2,5-Furandione, polymer with ethenylbenzene and 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

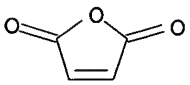
CM 1

CRN 2386-82-5
CMF C11 H8 F6 O



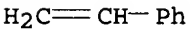
CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 100-42-5
CMF C8 H8



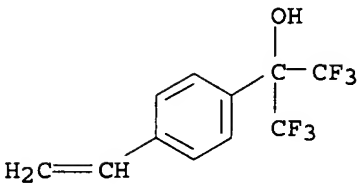
L10 ANSWER 4 OF 4 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1990:533845 CAPLUS
DN 113:133845
TI Aromatic polycarbonate-polystyrene compositions for optical materials
IN Takahashi, Yosuke; Oshima, Kensho; Sekimoto, Kenichi
PA Tosoh Corp., Japan
SO Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 02120355	A2	19900508	JP 1988-270939	19881028
PRAI JP 1988-270939		19881028		

AB The title compns., useful for optical recording materials such as digital audio disks, contain an aromatic polycarbonate and a copolymer of styrene 1-95, maleic anhydride (I) 1-50, and p-(H2C:CH)C6H4C(CF3)2OH (II) 1-50 mol %. A blend of 60 weight % bisphenol A polycarbonate (III) and 40 weight % 15:75:10 (mol) I-styrene-II copolymer gave injection-molded disks (thickness 1.2 mm) which showed light transmittance (500 nm) 90%, birefringence 4 nm, and heat distortion temperature 125°, vs. 90, 50, and 130, resp., for III.
IT **129558-09-4**
RL: USES (Uses)
(blends with aromatic polycarbonates, transparent, for optical materials)
RN 129558-09-4 CAPLUS
CN 2,5-Furandione, polymer with ethenylbenzene and 4-ethenyl-α,α-bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

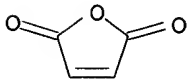
CM 1

CRN 2386-82-5
CMF C11 H8 F6 O



CM 2

CRN 108-31-6
CMF C4 H2 O3



CM 3

CRN 100-42-5
CMF C8 H8

$H_2C{=}CH{-}Ph$

=>

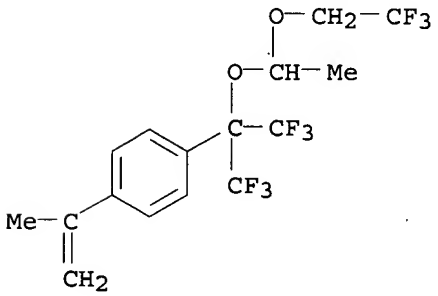
L11 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:40248 CAPLUS
DN 138:115049
TI Chemically amplified positive photoresist fluoropolymer compositions with high resolution and transparency to F2 excimer laser beams, and their deposition method
IN Kanna, Shinichi; Mizutani, Kazuyoshi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 44 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2003015301	A2	20030117	JP 2001-203565	20010704
PRAI JP 2001-203565		20010704		

AB The compns. comprise (A) fluoropolymers, which increase their alkali-solubility in the presence of acids, having repeating units I (R1 = H, F, alkyl; R2, R3 = H, OH, halo, cyano, alkoxy, aryl, etc.; R4 = H, alkyl, acyl, R5R6COR7, etc.; R5, R6 = H, alkyl, cycloalkyl; R7 = alkyl, cycloalkyl, aralkyl, aryl), (B) photoacid generators, and (C) solvents, wherein the compns. are heated at 110-150° in deposition.
IT **462109-91-7P 487048-79-3P**
RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PYP (Physical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
(F-containing styrene polymers for chemical amplified pos. photoresists with high resolution and transparency to F2 excimer laser beams)
RN 462109-91-7 CAPLUS
CN 2-Propenenitrile, 2-methyl-, polymer with 1-(1-methylethenyl)-4-[2,2,2-trifluoro-1-[1-(2,2,2-trifluoroethoxy)ethoxy]-1-(trifluoromethyl)ethyl]benzene and 1-(2,2,2-trifluoroethyl)-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

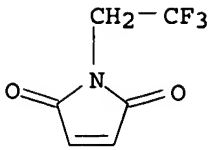
CM 1

CRN 462109-90-6
CMF C16 H15 F9 O2



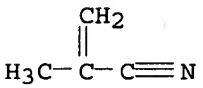
CM 2

CRN 771-52-8
CMF C6 H4 F3 N O2



CM 3

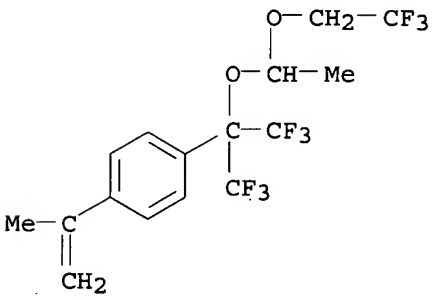
CRN 126-98-7
CMF C4 H5 N



RN 487048-79-3 CAPLUS
CN 2-Propenenitrile, 2-(fluoromethyl)-, polymer with 1-(1-methylethenyl)-4-[2,2,2-trifluoro-1-[1-(2,2,2-trifluoroethoxy)ethoxy]-1-(trifluoromethyl)ethyl]benzene and 1-(2,2,2-trifluoroethyl)-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

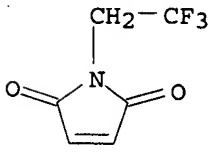
CM 1

CRN 462109-90-6
CMF C16 H15 F9 O2



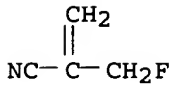
CM 2

CRN 771-52-8
CMF C6 H4 F3 N O2



CM 3

CRN 671-55-6
CMF C4 H4 F N



L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2002:734053 CAPLUS
DN 137:270514
TI Positive resist composition containing resin and photoacid generator
IN Aoai, Toshiaki; Mizutani, Kazuyoshi; Kanna, Shinichi
PA Fuji Photo Film Co., Ltd., Japan
SO Eur. Pat. Appl., 51 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 1243968	A2	20020925	EP 2002-6528	20020319
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
JP 2002351081	A2	20021204	JP 2002-74337	20020318
US 2002168584	A1	20021114	US 2002-99981	20020319
PRAI JP 2001-79184	A	20010319		

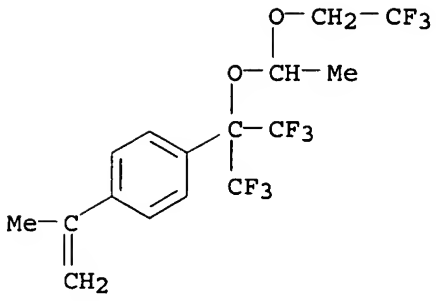
AB The present invention relates to a pos. resist composition used in micro-lithog processes for the manufacture of VLSI's and micro-tips with large capacities. The present invention relates to a pos. resist composition capable of forming fine patterns with use of a vacuum UV ray having a wavelength of < 160 nm. A pos. resist composition comprises: (A) a resin containing a specified repeating unit I (R1 = H, halogen atom, cyano group, alkyl; R2,3 = H, hydroxy group, halogen atom, cyano, alkoxy, acyl, alkyl, cycloalkyl, alkenyl, aralkyl, aryl; R4 = H, alkyl, perfluoroalkyl, cycloalkyl, acyl, alkoxyacrbonyl, etc.), which is capable of decomposing by the action of an acid to increase the solubility in an alkali developer; and (B) a compound capable of generating an acid upon irradiation with one of an actinic ray and a radiation.

IT **462109-91-7P**
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(resin and acid generator for pos. resist composition)

RN 462109-91-7 CAPLUS
CN 2-Propenenitrile, 2-methyl-, polymer with 1-(1-methylethenyl)-4-[2,2,2-trifluoro-1-[1-(2,2,2-trifluoroethoxy)ethoxy]-1-(trifluoromethyl)ethyl]benzene and 1-(2,2,2-trifluoroethyl)-1H-pyrrole-2,5-dione (9CI) (CA INDEX NAME)

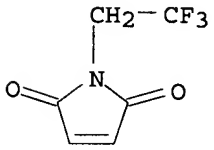
CM 1

CRN 462109-90-6
CMF C16 H15 F9 O2



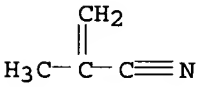
CM 2

CRN 771-52-8
CMF C6 H4 F3 N O2



CM 3

CRN 126-98-7
CMF C4 H5 N



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